

Plasma-enhanced atomic layer deposition for plasmonic TiN (Erratum)

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A revised version of this manuscript was published on 12 May 2020. Details of the revision are as follows:

Change 1: Table 1, Plasma 2 - gases were listed in the wrong order and so were flipped.

Change 2: Equation 1 - an incorrect negative sign was switched to a positive sign in the denominator of the Lorentz component.